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ATTORNEY DOCKET NO.: 04329.2409

Box Patent Application Assistant Commissioner for Patents Washington, D.C. 20231

New U.S. Patent Application

Title: PATTERN CORRECTING METHOD OF MASK FOR MANUFACTURING A SEMICONDUCTOR DEVICE AND RECORDING MEDIUM HAVING RECORDED ITS PATTERN CORRECTING METHOD Inventors: 1) Kei YOSHIKAWA, 2) Satoshi USUI and 3) Koji HASHIMOTO

Sir:

We enclose the following papers for filing in the United States Patent and Trademark Office in connection with the above patent application.

- A check for \$1120.00 representing a \$1080.00 filing fee and \$40.00 for 1. recording the Assignment.
- Application 60 pages, including 8 independent claims and 14 claims 2. total.
- 3. Drawings - 30 sheets of formal drawings containing 67 figures.
- 4. Declaration and Power of Attorney.
- 5. Recordation Form Cover Sheet and Assignment to Kabushiki Kaisha Toshiba.
- Certified copy of Japanese Patent Application No. 11-260270, filed on 6. September 14, 1999.



FINNEGAN, HENDERSON, FARABOW, GARRETT & DUNNER, L.L. P.

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7. Information Disclosure Statement and Information Disclosure Citation, PTO 1449 with documents attached.

Applicants claim the right to priority based on Japanese Patent Application No. 11-260270, filed on September 14, 1999.

Please accord this application a serial number and filing date and record and return the Assignment to the undersigned.

The Commissioner is hereby authorized to charge any additional filing fees due and any other fees due under 37 C.F.R. § 1.16 or § 1.17 during the pendency of this application to our Deposit Account No. 06-0916.

Respectfully submitted,

FINNEGAN, HENDERSON, FARABOW, GARRETT & DUNNER, L.L.P.

Bv:

Richard DBurgujian

RVB/FPD/sci Enclosures